Gamma Operation Instructions

Enable the tool in NEMO, then log into the software as "user" with password "cnf".

Turn ON the two **Nitrogen** switches <u>ONLY</u> if coating with resist or ARC, not for development.

Click "**INIT**" button.

Press the **I/O Door Interlock** to unlock the door and remove the wafer cassette.

Place the loaded wafer cassette in either load station making sure that the H-bar sits in the slot, all wafers are seated, then close the door and press the **I/O Door Interlock** to lock the door.

<u>**IMPORTANT:**</u> Load wafers with <u>major flats</u> at the <u>bottom</u> of the cassette, <u>facing out of the tool</u> when loaded. You can use the flat finder tool. Be careful not to cross-slot wafers.

Click on the **Jobs** button at the bottom of the screen, then click the **Load Carrier** button for the load station in use. The tool will detect the wafers and select all by default.

Click **Select Substrates** to change which wafers are selected.

Click **Select Sequence** to choose the program to run. <u>Do not</u> click <u>**Add** Sequence</u> unless you want to run programs sequentially without stopping between programs (NOT recommended).

Nozzle Clean (1030) <u>**MUST**</u> be run before coating wafers with automatically dispensed material. Run the job using a single wafer. Repeat until nozzle streams are normal. <u>Pre-rinsing the nozzles using Acetone is recommended before running the cleaning job.</u>

Click **Start Sequence** to start the program. Hotplate temperature ramp may delay start.

Run at least 1 dummy wafer first in ARC or photoresist coating jobs. If you see problems with the dummy, the remaining wafers can be prevented from processing by using the **Input Stop** button on the right side of the **Jobs** screen.

<u>Standard program for DUV ARC</u> is **1002** (DUV42P @ 62nm). **Nitrogen** should be ON.

<u>Standard programs for DUV photoresist</u> are **1003** (UV210 @ 0.6μm) and **1009** (UV210 @ 0.5μm). **Nitrogen** should be ON.

<u>Standard program for DUV development</u> is **2010** (135°C 90 sec, 726 MIF 60 sec.). No dummy wafers are necessary. **Nitrogen** switches should be OFF.

When program completes, unlock door and remove wafers. Replace cassette and press the **I/O Door Interlock** to lock the door. Turn OFF N_2. Log out of software, then log out of NEMO.

Troubleshooting:

Stranded wafers from failed jobs can be removed manually:
Click the **Pause** button on upper right of main screen.
Hold the left mouse button to drag each wafer to the desired module and click OK.